

Single-Wafer Process Support

Single-wafer processing has become increasingly popular, but this method of processing is challenging. Supporting multiple, single-wafer chambers with the same tool requires rapid flow changes that are unpredictable.

Trebor was approached by a customer who needed to heat a liquid to $\pm 1^\circ\text{C}$ during aggressive flow changes. A Trebor design team collaborated closely with the customer's process engineering department and the results were impressive – an innovative heating system using Trebor's IQ heaters and a specially designed controller. The final system tested at less than $\pm 0.5^\circ\text{C}$ with flow changes up to 250%.

Trebor's IQ chemical heater design is unique for this type of application due to its small package, fast reaction (low thermal mass), and innovative controls. Trebor delighted the customer and exceeded expectations with collaborative engineering and innovative designs.

Construction

- ▶ Quartz/PFA fluid path for clean operation
- ▶ Multiple fitting options to adapt to any application
- ▶ No metal contamination risk
- ▶ No particle traps
- ▶ SEMI S2, S3, and CE certified
- ▶ One-year warranty

Performance Summary

IQL — Low Temperature	English	Metric
▶ Maximum Pressure	80 psig	.55 MPa
▶ Maximum Chemical Operating Temperature	212 °F	100 °C
IQH — High Temperature	English	Metric
▶ Maximum Pressure	45 psig	.31 MPa
▶ Maximum Chemical Operating Temperature	392 °F	200 °C



Heating modules may be combined to achieve desired capacity.

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